

### Rough Polish – Pad Dresser Application

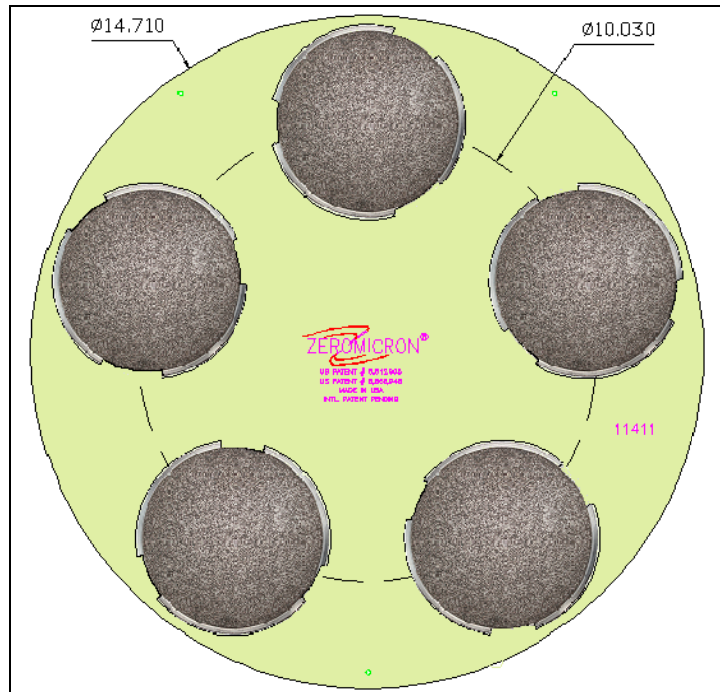
This application note applies to the first stage or rough polish process. Typically these are polishing pads with a larger, more rigid cell structure that are used for rapid material removal.

A five “puck”, 14.710 inch diameter pad dresser is pictured at the right.

These templates use a 4.25 inch “puck” manufactured by 3M Corporation that has diamonds bonded to the surface.

The “puck” is mounted in a G-10 holder that allows it to rotate freely.

The “pucks” are modified by ZeroMicron for this application.



Instructions for the application of the diamond disk pad dresser (for rough polishing pad):

1. Remove wax paper to expose the adhesive and mount the diamond disk pad dresser to the carrier.
2. Install the carrier and set up the tool for normal operating conditions for platen and carrier rotation.
3. Start the tool and apply 1 to 2 psi pressure on the carrier when conditioning.
4. Condition for 3 minutes with DI water at a flow rate of 300 to 500 mL per minute.

Note: For a process that polishes hard substrates like sapphire or silicon carbide, some of our customers condition the pad after every run. Softer materials may require less frequent conditioning. Frequency of conditioning is dependent on the polishing pad performance as measured by the removal rate.

5. After conditioning, spray DI water onto the polishing pad to flush all residue off.
6. After use, spray and rinse the diamond disk pad dresser thoroughly and store the diamond disk pad dresser with the diamond pucks face down to allow the water to drain off.

For additional information or assistance, please contact ZeroMicron Inc. directly.

ZeroMicron Inc.  
2330 South Tenth Street  
San Jose, CA 95112  
Tel: (408) 441-4600  
Fax: (408) 441-4602  
[Sales@ZeroMicron.com](mailto:Sales@ZeroMicron.com)  
[www.ZeroMicron.com](http://www.ZeroMicron.com)